

Appl. No. : 09/037,945
Filed : March 10, 1998

removing the mask after growing the field oxide; and
forming a gate oxide of uniform thickness adjacent the field oxide on the semiconductor substrate without performing a prior sacrificial oxidation.

15. (Newly Added) The process of Claim 14, wherein the growing the field oxide comprises exposing the substrate to a hydrogen-free oxidant.

16. (Newly Added) The process of Claim 15, wherein growing the field oxide further comprises maintaining the oxidant partial pressure at about 5-30 atm.

17. (Newly Added) The process of Claim 15, wherein growing the field oxide further comprises maintaining the substrate at greater than about 900°C.

REMARKS

Applicant respectfully submits that the amendments are fully supported by the specification and drawings as filed, and that the amendments place the application in better condition for allowance.

Applicants submit that the art of record does not teach or suggest the inventions as claimed. Dry oxidation as a method of growing silicon dioxide is known, as disclosed, for example, Marshall et al, cited in the parent application (Serial No. 08/519,451, filed August 25, 1995) and in the Information Disclosure Statement filed herewith. None of the art of record, however, taught or suggested dry or hydrogen-free oxidation in combination with the omission of sacrificial oxidation in a fabrication process as recited, for example, in independent Claims 1 and 13. Moreover, the none of the art of record taught forming field oxide in integrated circuits by dry oxidation alone, or without further wet oxidation, at the pressure ranges recited in independent Claims 8 and 11, for example. Accordingly, Applicants submit that the claims are patentably distinct from the art of record.

CONCLUSIONS

In view of the foregoing amendments and remarks, Applicants submit that the application is in condition for examination on the merits. Applicants further submit that the application is in condition for allowance, and respectfully request the same. If, however, the Examiner feels that

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a telephonic interview would further prosecution of the application, the Examiner is invited to call the undersigned for such telephonic interview.

Respectfully submitted,

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Dated: June 10, 1998

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